Call for Papers – DPS 2017

39th International Symposium on Dry Process

November 16(Thu) – 17(Fri), 2017
Tokyo Tech Front (Kuramae Kaikan),
Tokyo Institute of Technology, Tokyo, Japan

Paper Submission Deadline: July 14, 2017
For author instructions and information about DPS at:
http://www.dry-process.org/2017/

The 39th International Symposium on Dry Process (DPS2017) will be held at Tokyo Tech Front (Kuramae Kaikan), Tokyo Institute of Technology, Tokyo, in Japan, on November 16 & 17, 2017.
The Symposium covers all aspects of the rapidly evolving fields of dry processes, including but not limited to plasma etching and deposition processes, diagnostics and modeling of plasmas and surfaces, and surface modifications by plasmas, for the applications in, e.g., microelectronics, power devices, sensors, environmental protection, biological systems, and medicine. The DPS has provided valuable forums for in-depth discussion among professionals and students working in this exciting field for more than three decades.

Theme: Dry processes and related technologies from fundamentals to applications

Topics:

1. Etching Technologies
2. Manufacturing Technologies (AEC, APC, EES, FDC)
3. Surface Reaction and Damage
4. Plasma Diagnostics and Monitoring Systems
5. Modeling and Simulation
6. Plasma Generation (Equipment/Source)
7. Deposition Technologies (CVD / PVD)
8. Atomic Layer Processes (ALD/ALE)
9. Plasma Processes for 3D Device, FPD, Photovoltaic Devices
10. Plasma Processes for New Material Devices (MRAM, Power, Organic)
11. Plasma Processes for Biological and Medical application, MEMS
12. Atmospheric Pressure Plasma and Liquid Plasma
13. New Dry Process Concepts

Arranged session:

A1. Surface reactions for atomic layer controlled processes (ALE/ALD)
A2. Etching technologies for latest devices having high-aspect-ratio of 50 or more (HAR）

For further general information, please contact:

e-mail:dps2017@officepolaris.co.jp

Organizing Committee Chair: Keizo Kinoshita (PETRA)
Executive Committee Chair: Hiroshi Akatsuka (Tokyo Institute of Technology)
Program Committee Chair: Miyako Matsui (Hitachi, Ltd.)
Publication Committee Chair: Kazuhiro Karahashi (Osaka University)

URL: http://www.dry-process.org/2017/

DPS 2017 is co-sponsored by The Japan Society of Applied Physics

The Japan Society of Applied Physics